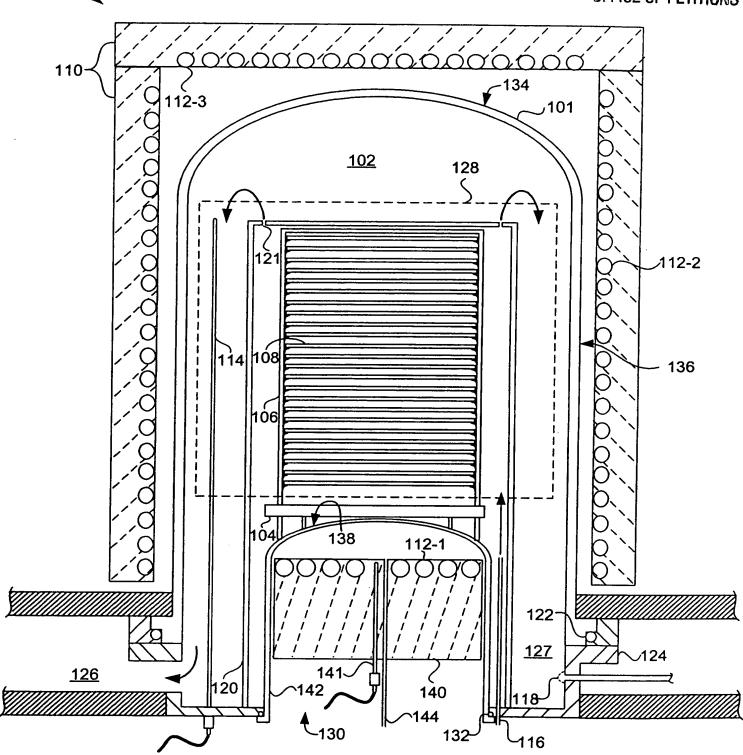
RECEIVED

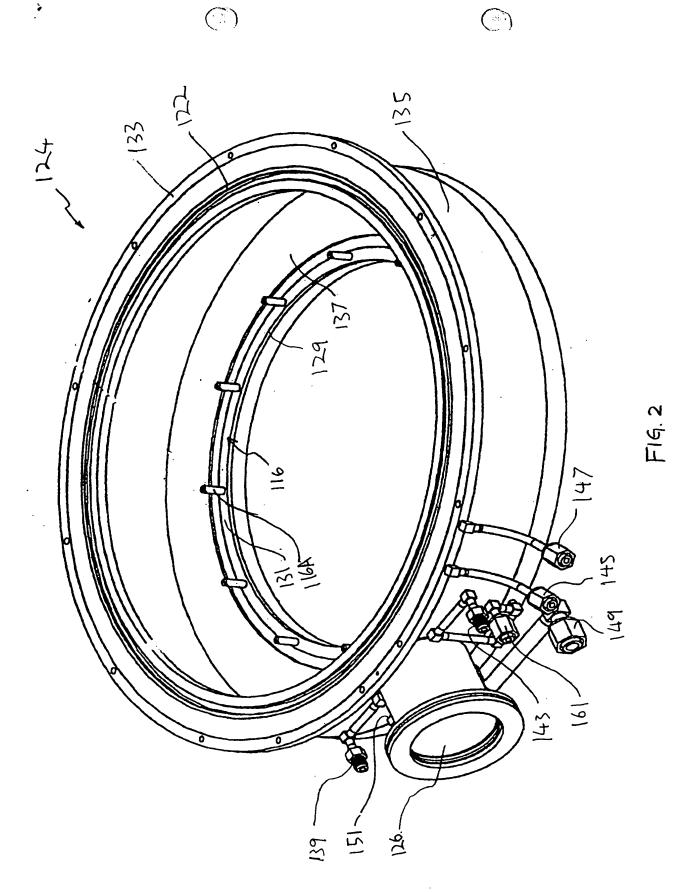
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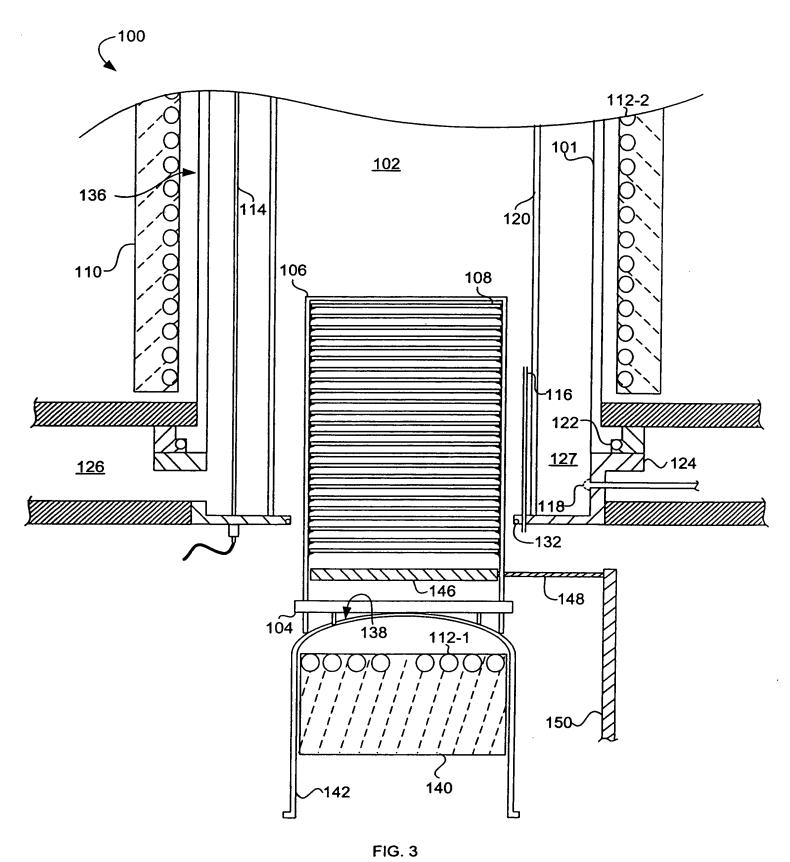
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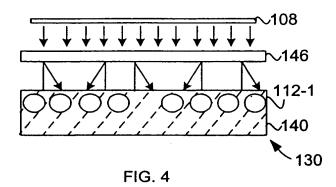


-100

FIG. 1







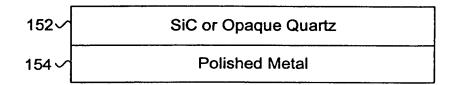


FIG. 5

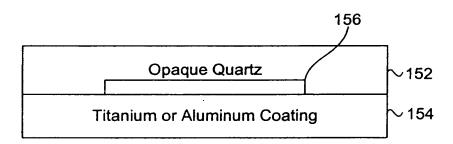
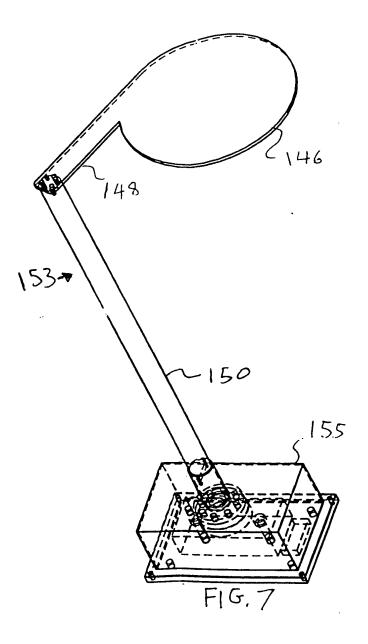


FIG. 6



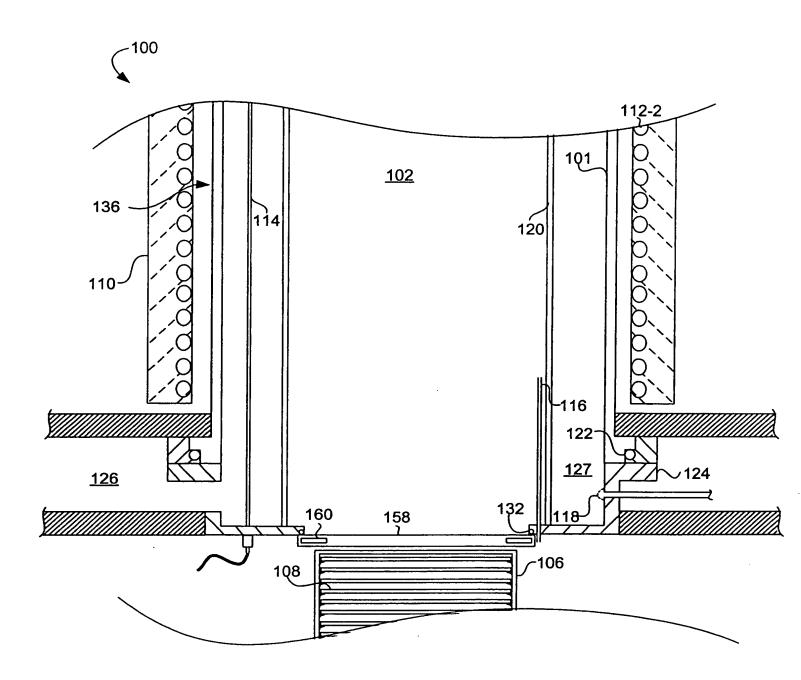


FIG. 8

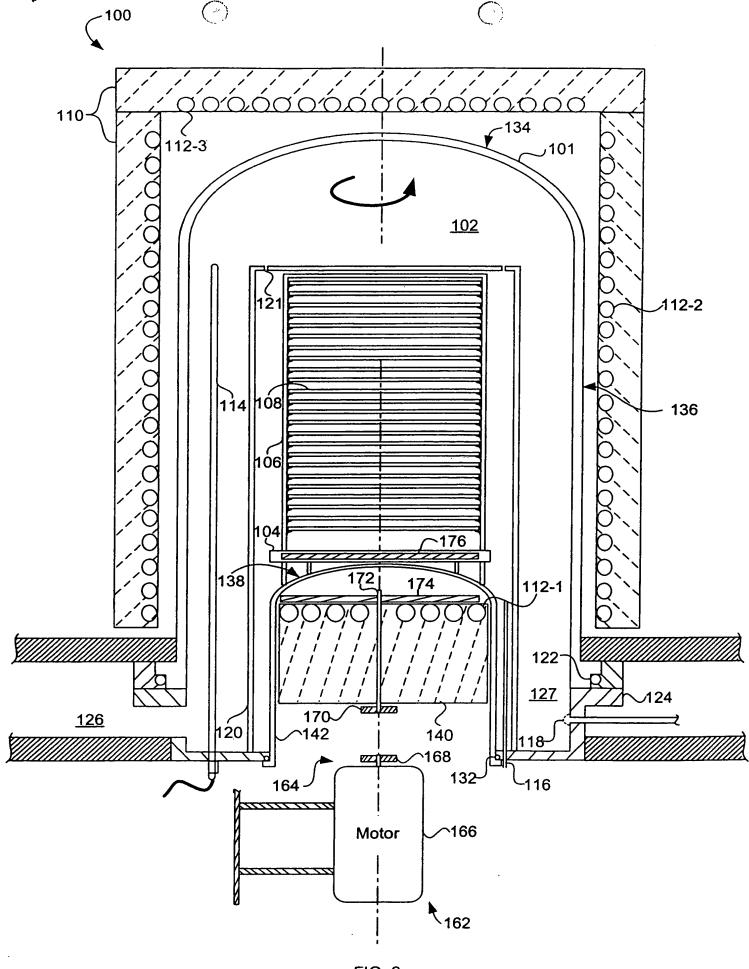


FIG. 9

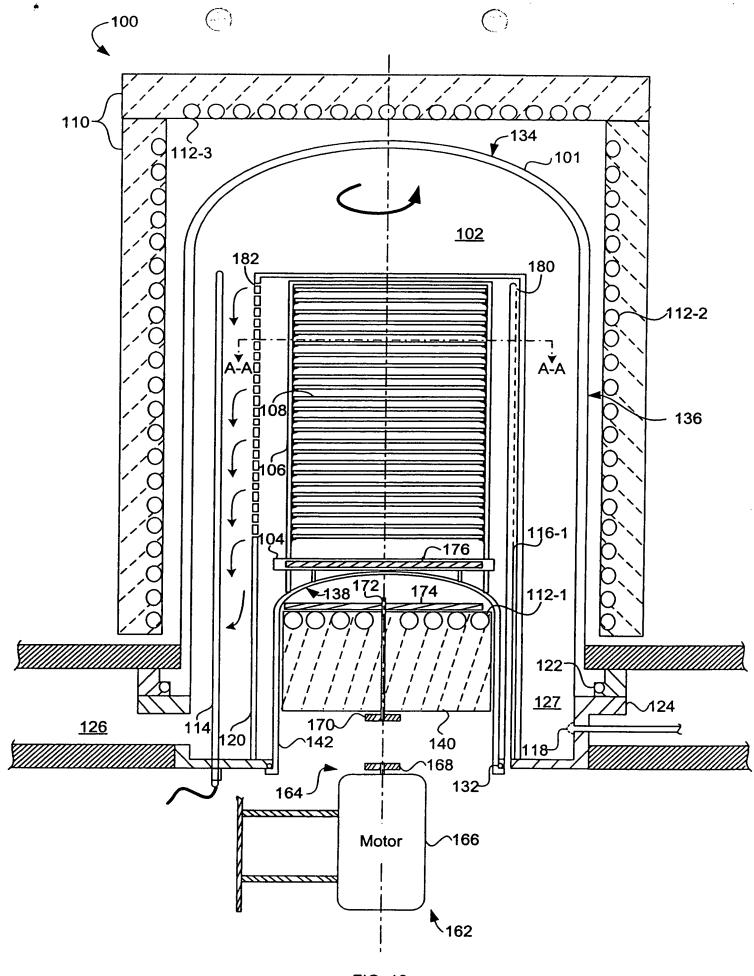
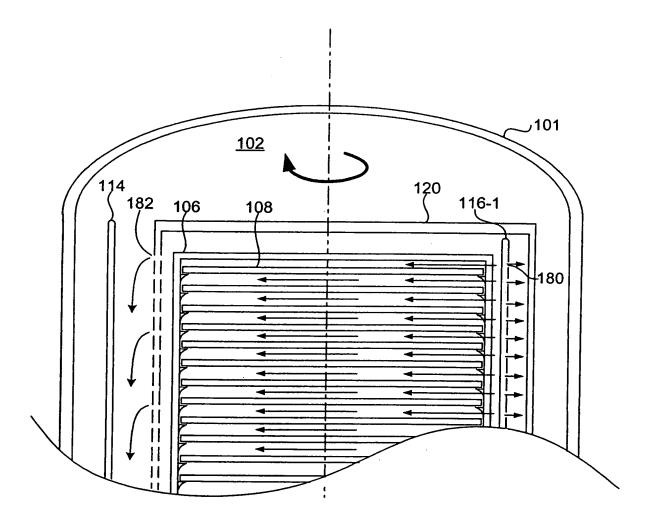


FIG. 10



1

FIG. 11

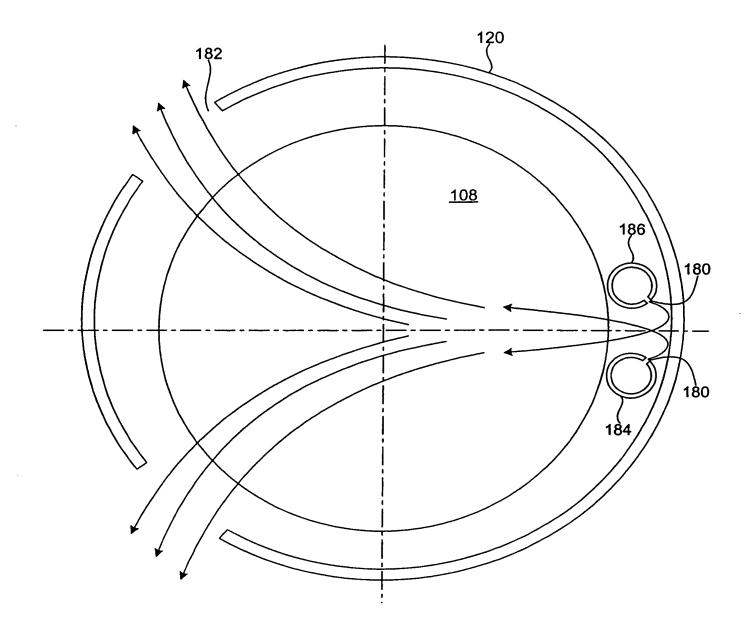


FIG. 12

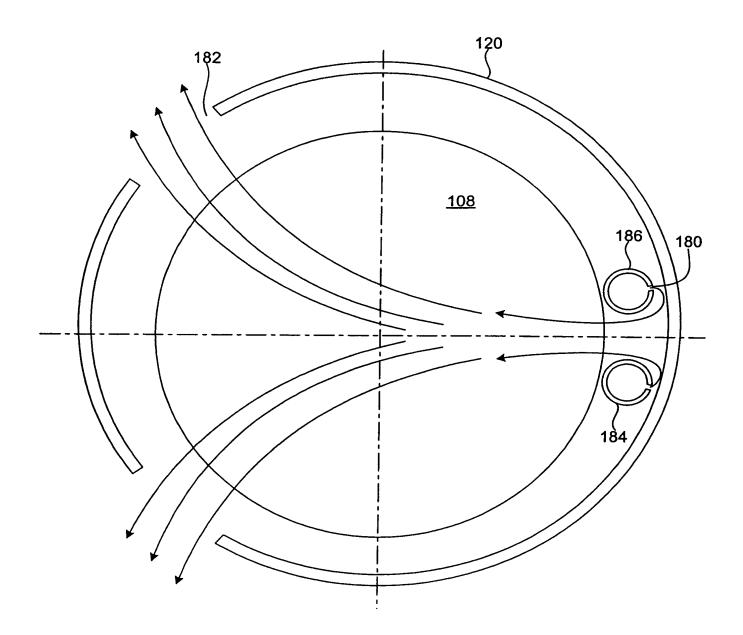


FIG. 13

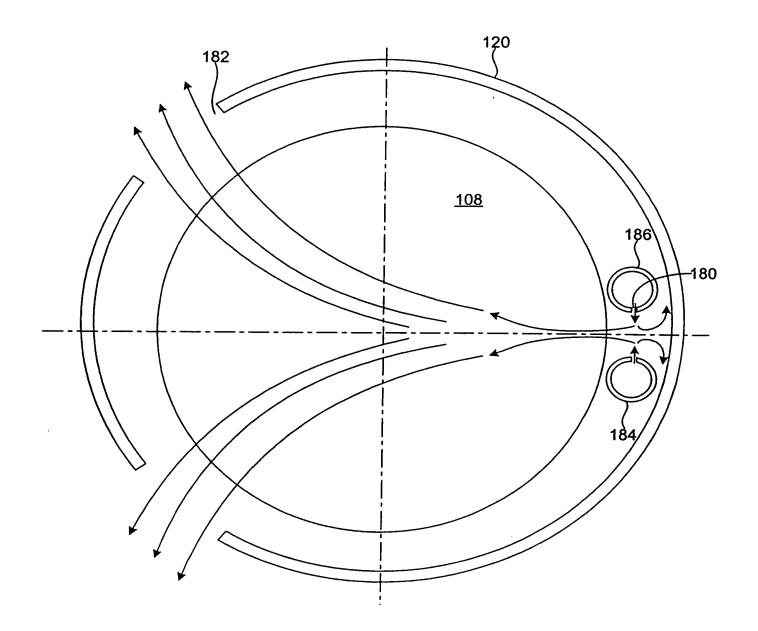


FIG. 14

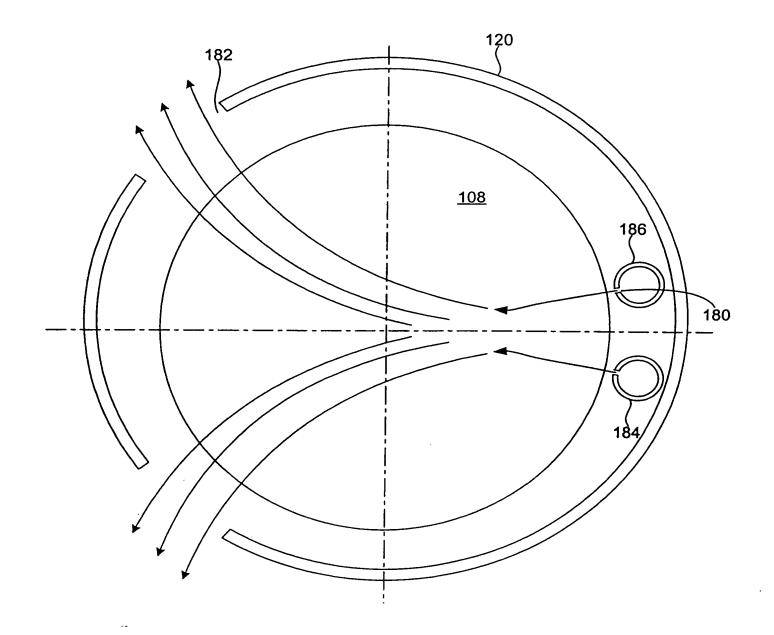


FIG. 15

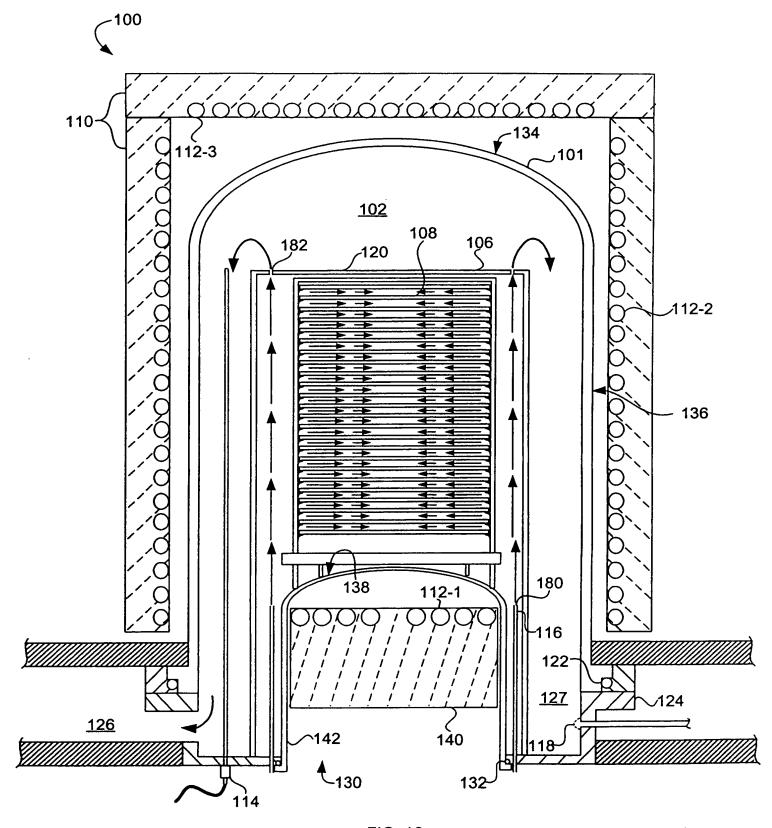
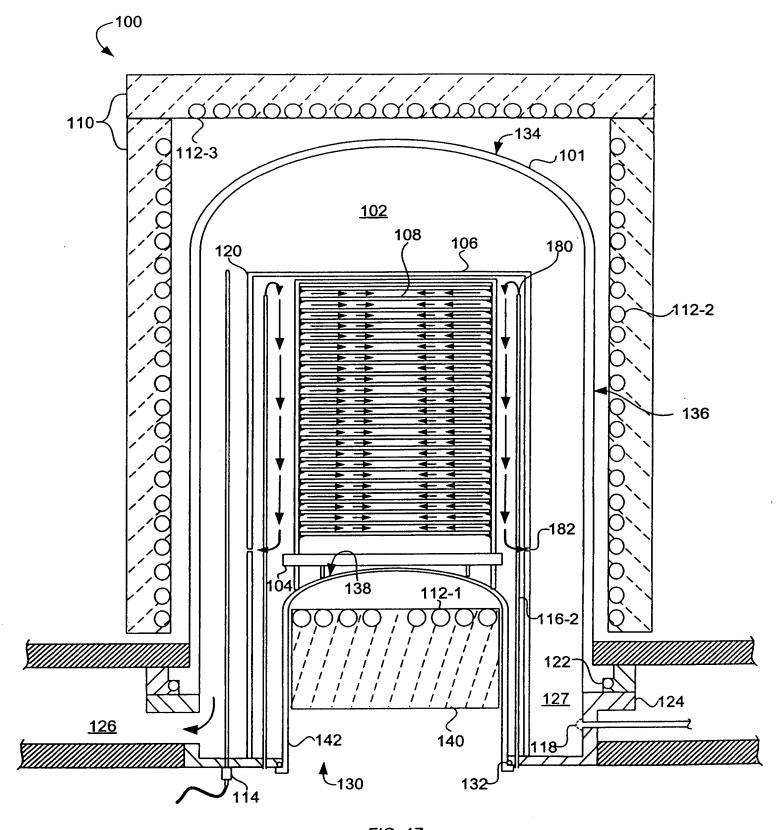


FIG. 16



(\$<sup>1</sup>\$.,

FIG. 17



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LOWER PEDESTAL AND POSITION THERMAL SHIELD TO MAINTAIN THE TEMPERATURE OF THE PEDESTAL AND TO INSULATE THE WAFERS

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MOVE THE SHUTTER INTO POSITION TO ISOLATE THE PROCESS CHAMBER

194

192

APPLY POWER TO THE HEATING ELEMENTS TO PRE-HEAT OR MAINTAIN THE TEMPERATURE OF THE PROCESS CHAMBER

196

## POSITION THE CARRIER ON THE PEDESTAL

197

RAISE THE PEDESTAL TO POSITION THE BOAT IN THE PROCESS ZONE WHILE SIMULTANEOUSLY REMOVING THE SHUTTER AND THE THERMAL SHIELD PREHEATING THE WAFERS IN THE CARRIER TO AN INTERMEDIATE TEMPERATURE

198>

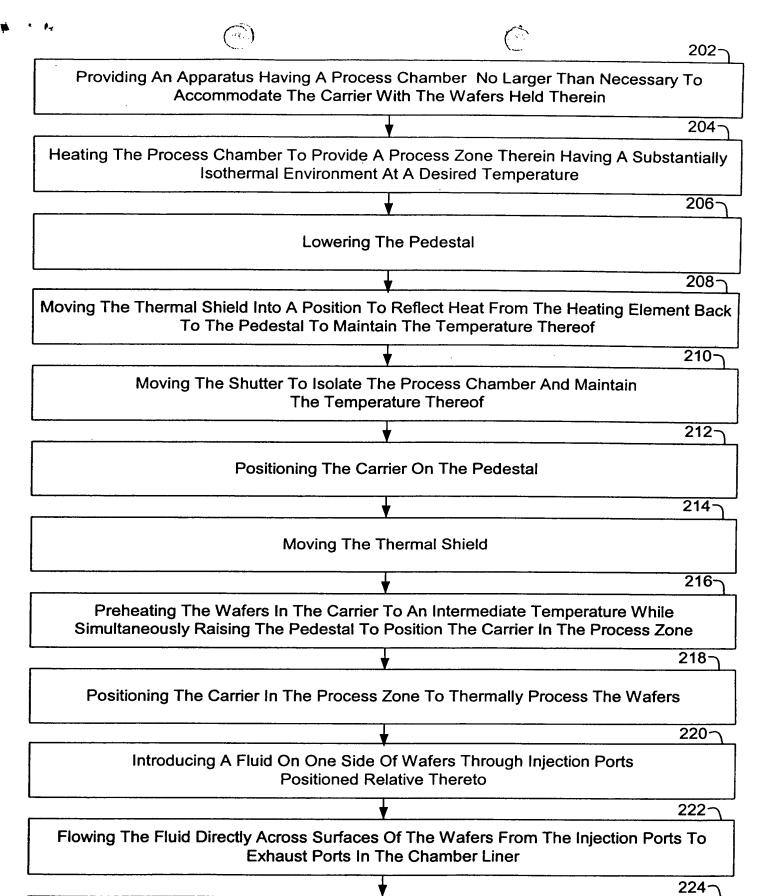
INTRODUCE A FLUID ON ONE SIDE OF THE PLURALITY OF WAFERS THROUGH A PLURALITY OF INJECTION PORTS

199

FLOW THE FLUID FROM THE INJECTION PORTS ACROSS SURFACES OF THE WAFERS TO EXHAUST PORTS POSITIONED IN THE LINER ON THE OPPOSITE SIDE OF THE WAFERS RELATIVE TO THE INJECTION PORTS

200

MAGNETICALLY COUPLE MECHANICAL ENERGY THROUGH THE PEDESTAL TO THE CARRIER TO REPOSITION THE CARRIER DURING THERMAL PROCESSING OF THE WAFERS



Magnetically Coupling Mechanical Energy Through The Pedestal To The Carrier To Reposition The Carrier During Thermal Processing Of The Wafers